

## RETRACTION

[View Article Online](#)  
[View Journal](#) | [View Issue](#)

Cite this: RSC Adv., 2021, 11, 30703

DOI: 10.1039/d1ra90145a

[rsc.li/rsc-advances](http://rsc.li/rsc-advances)

## Retraction: Magnetic $\text{Fe}_3\text{O}_4@\text{NiO}$ hierarchical structures: preparation and their excellent As(v) and Cr(vi) removal capabilities

Shouwei Zhang,<sup>ab</sup> Jiaxing Li,<sup>b</sup> Tao Wen,<sup>b</sup> Jinzhang Xu<sup>\*a</sup> and Xiangke Wang<sup>\*b</sup>Retraction of 'Magnetic  $\text{Fe}_3\text{O}_4@\text{NiO}$  hierarchical structures: preparation and their excellent As(v) and Cr(vi) removal capabilities' by Shouwei Zhang *et al.*, RSC Adv., 2013, 3, 2754–2764, DOI: 10.1039/C2RA22495J.

The Royal Society of Chemistry, with the agreement of the named authors, hereby wholly retracts this *RSC Advances* article due to concerns with the reliability of the data in the published article. The authors requested to retract this article because they admitted that the TEM characterization of the  $\text{Fe}_3\text{O}_4@\text{NiO}$  hierarchical microspheres in Fig. 4c was duplicated from the characterization of  $\text{Fe}_3\text{O}_4@\text{NiAl-LDH}$  microspheres in Fig. S4B from a *J. Am. Chem. Soc.* paper by Mingfei Shao *et al.* without permission.<sup>1</sup> The authors would like to apologise to the authors of ref. 1, and for any inconvenience to readers.

Signed: Shouwei Zhang, Jiaxing Li, Jinzhang Xu and Xiangke Wang

Date: 11th August 2021

Tao Wen was contacted but did not respond

Retraction endorsed by Laura Fisher, Executive Editor, *RSC Advances*

## References

- 1 M. Shao, F. Ning, J. Zhao, M. Wei, D. G. Evans and X. Duan, *J. Am. Chem. Soc.*, 2012, **134**(2), 1071–1077.

<sup>a</sup>School of Material Science and Engineering, Hefei University of Technology, Hefei, 230031, P. R. China<sup>b</sup>Key Laboratory of Novel Thin Film Solar Cells, Institute of Plasma Physics, Chinese Academy of Sciences, P.O. Box 1126, Hefei, 230031, P. R. China. E-mail: xkwang@ipp.ac.cn; Fax: +86-5515591310; Tel: +86-551-5592788